# AIChE JOURNAL

OCTOBER 1988 • VOL. 34, NO. 10

**The AIChE JOURNAL, a monthly publication of the American Institute of Chemical Engineers, is devoted to fundamental research and developments having immediate or potential value in chemical engineering.**

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1987 488 pp ISBN 0-8196-0427-8 LC87-81560
*Pub P-50 Hardcover AIChE Members $40 Others $60*

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*AIChE Journal* (ISSN 0001-1541) is published monthly by the American Institute of Chemical Engineers, 345 E. 47th St., New York, NY 10017. Manuscripts should be submitted to Editor Morton M. Denn, at the Dept. of Chemical Engineering, University of California, Berkeley, CA 94720, Phone (415) 643-6591. The statements and opinions in the *AIChE Journal* are those of the contributors, and AIChE assumes no responsibility for them. Annual subscription rates: $275 for nonmembers, $40 for members; outside U.S., add $13 for postage. Single copies: $30; outside U.S., add $2 for postage. Second-class postage paid at New York, NY and additional mailing offices. Copyright 1988 by the American Institute of Chemical Engineers. Subscribers are requested to give prompt notification of any change of address. Postmaster: Send changes of address to *AIChE Journal*, 345 East 47th St., New York, NY 10017.

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